

United States Patent Application Serial No. 09/551,018
Attorney Docket No. 478

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:

Applicants: Chongying Xu, et al.

Serial No: 09/551,018

Date Filed: April 18, 2000

Title: Silicon Reagents and Low Temperature CVD
Method of Forming Silicon-Containing Gate
Dielectric Materials Using Same

Group Art Unit: 1714


Examiner: Cephia D. Toomer

Confirmation No.: 2050

Customer No.: 25559

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**AMENDMENT RESPONDING TO JULY 11, 2003 FINAL OFFICE ACTION IN U.S.
PATENT APPLICATION NO. 09/551,018 AND
REQUEST FOR CONTINUED EXAMINATION UNDER 35 U.S.C. § 132**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated July 11, 2003, Applicant respectfully requests entry of the following Amendments and consideration of the subsequent remarks.